XP-002276694

AN - 1978-14697A [08]
A - [001] 011 03- 040 074 081 139 185 189 23- 231 273 311 341 359 398 427 431 432 47& 473 477 532 537 57- 656 688 721 726
CPY - TOSH-I
DC - A32 G02 M11 P42
FS - CPI;GMPI
IC - B05D3/00 ; B05D7/14 ; C25D11/22 ; C25D13/04
KS - 0218 0229 0486 1276 1737 2020 2198 2297 2299 2378 2420 2422 2427 2439 2493 2509 2575 2728 2796
MC - A11-B05A A12-B04B G02-A02B M11-E01 M11-G
PA - (TOSH-I) TOSHIYUKI O
PN - JP53001651 A 19780109 DW197808 000pp
PR - JP19760076236 19760628
XIC - B05D-003/00 ; B05D-007/14 ; C25D-011/22 ; C25D-013/04
AB - J53001651 Method comprises anodising an Al surface to form an anodic oxide film; dipping in a weak alkali soln. to form hydroxide in the holes of the anodic oxide film as a sealing treatment; subjecting to an electrodeposition coating process and baking the formed coating by heating.
- In an example, an Al plate was anodised in a 15% H2SO4 soln. for 15 mins. at a current density of 1 A/dm2. Then, The Al plate was subjected to an anodic pigmentation process in a bath contg. sulphosalicylic acid is 2%, sulphamine is 1% and H2SO4 is 0.2%, for 10 mins. with 50-80 V, after washing the Al plate with water. The Al plate was dipped n an alkali soln. the pH of which was adjusted to 7 by adding triethylamine, for 10 mins. The al plate was treated with hot water (80 degrees C) for 2 mins., and was dipped in a water soluble acrylic melamine resin (10%) paint (coating) for 2 mins. at 150 V. The Al plate was then heated to 180 degrees C for 10 mins to bake the formed coatings.
IW - COATING ALUMINIUM ELECTRODEPOSIT ANODISE FORMING HYDROXIDE HOLE ANODISE SURFACE COATING BAKE
IKW - COATING ALUMINIUM ELECTRODEPOSIT ANODISE FORMING HYDROXIDE HOLE ANODISE SURFACE COATING BAKE
NC - 001
OPD - 1976-06-28
ORD - 1978-01-09
PAW - (TOSH-I) TOSHIYUKI O
TI - Coating aluminium by electrodeposition - by anodising, forming hydroxide in holes of anodised surface, coating and baking